

DE LA RECHERCHE À L'INDUSTRIE

Development of Micro-Time-Of-Flight mass spectrometer for *in situ* gas analysis

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Environment
(O_3 , NOX, CH_4 ,...)

Large variety of chemicals
to detect:
Need a fast, versatil,
accurate, sensitive and
portable analytical system

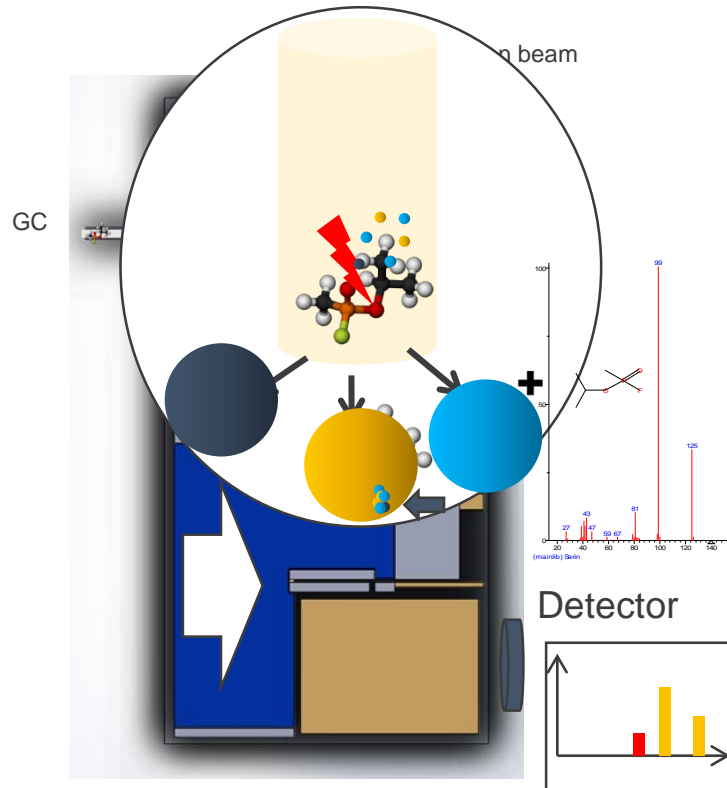
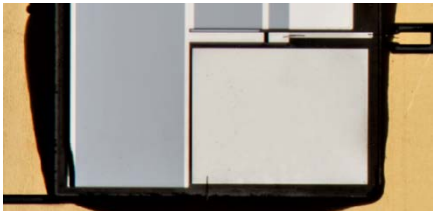


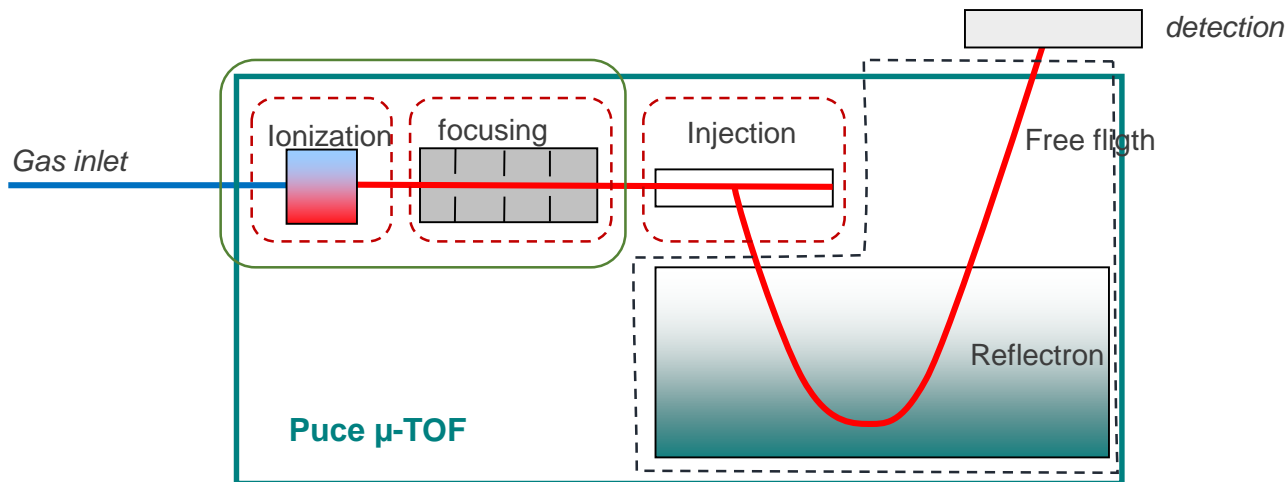
Chemical Industry
(pesticid



Mass Spectrometry

- ① Gas injection from μ -GC or GC
- ② Ionization and molecule fragmentation by Electron Impact
- ③ Ion extraction and focusing
- ④ Orthogonal injection
- ⑤ Energy focusing by reflectron
- ⑥ Ion free flight and detection
- ⑦ Comparison with spectra database and compound identification



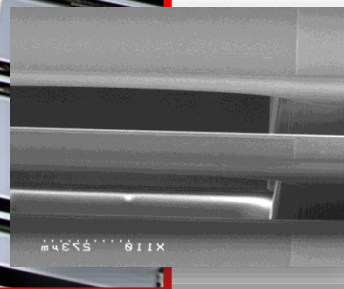
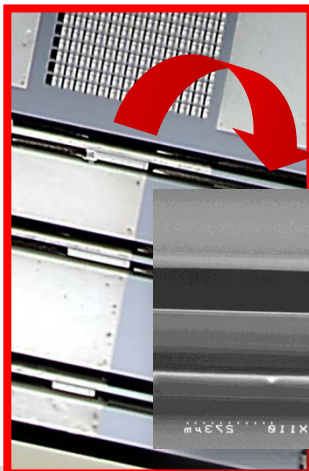
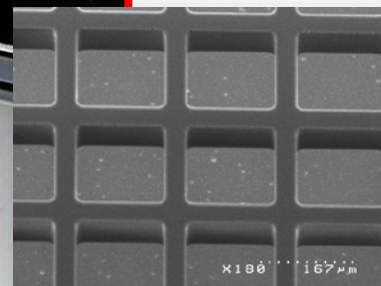
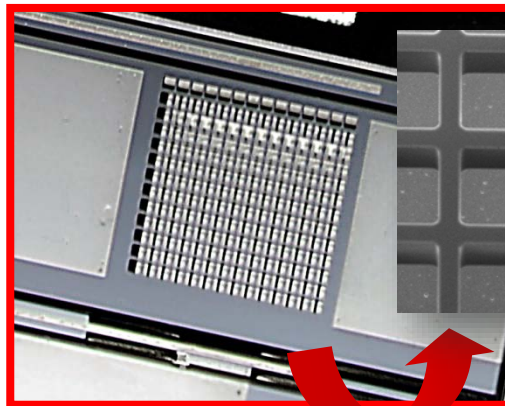
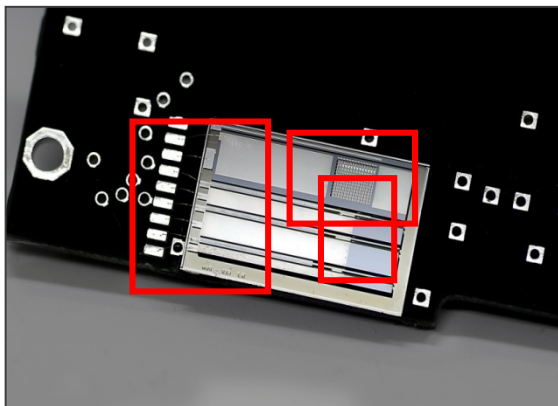


4 areas

- Ionization
- Ion extraction / focusing area
- Orthogonal Injection
- Free flight

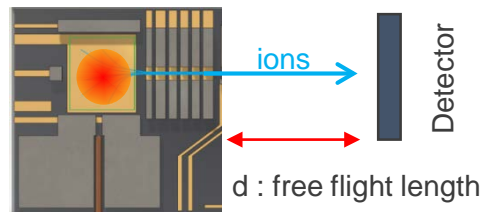
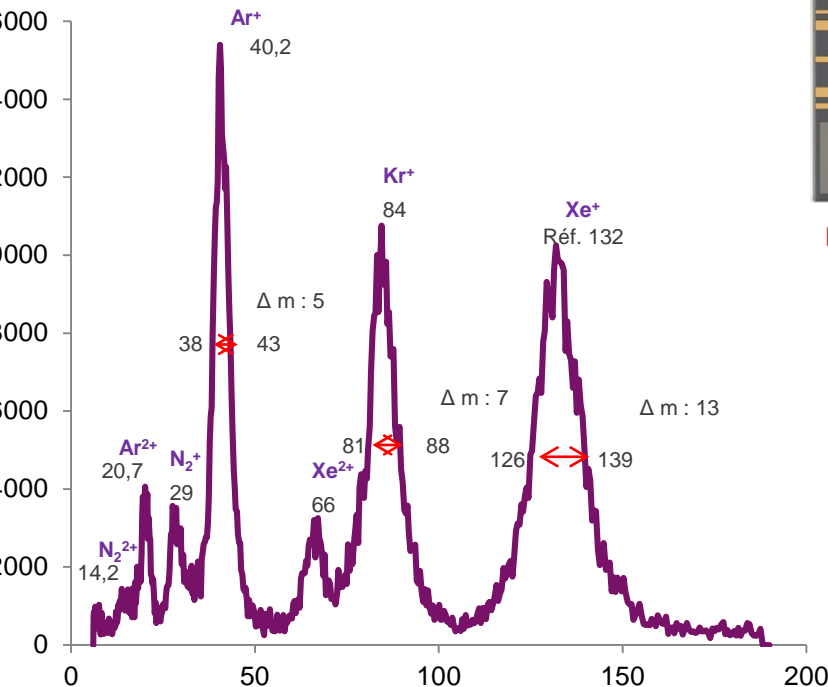
Linear micro-mass spectrometer

- Pulse out of chip, on the cover,
- Detection by MCP,
- Acquisition by Oscilloscope Tektronics DPO7254C



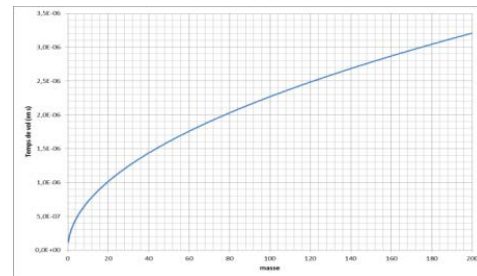
- Ionization Area
- Bonding
- Electrostatic lens

*Chip check by SEM
(Scanning Electron
Microscopy)*



■ Pulse electron beam

$$t_{flight} = \frac{d}{2\sqrt{U}} \sqrt{\frac{M_a M_p}{q}}$$



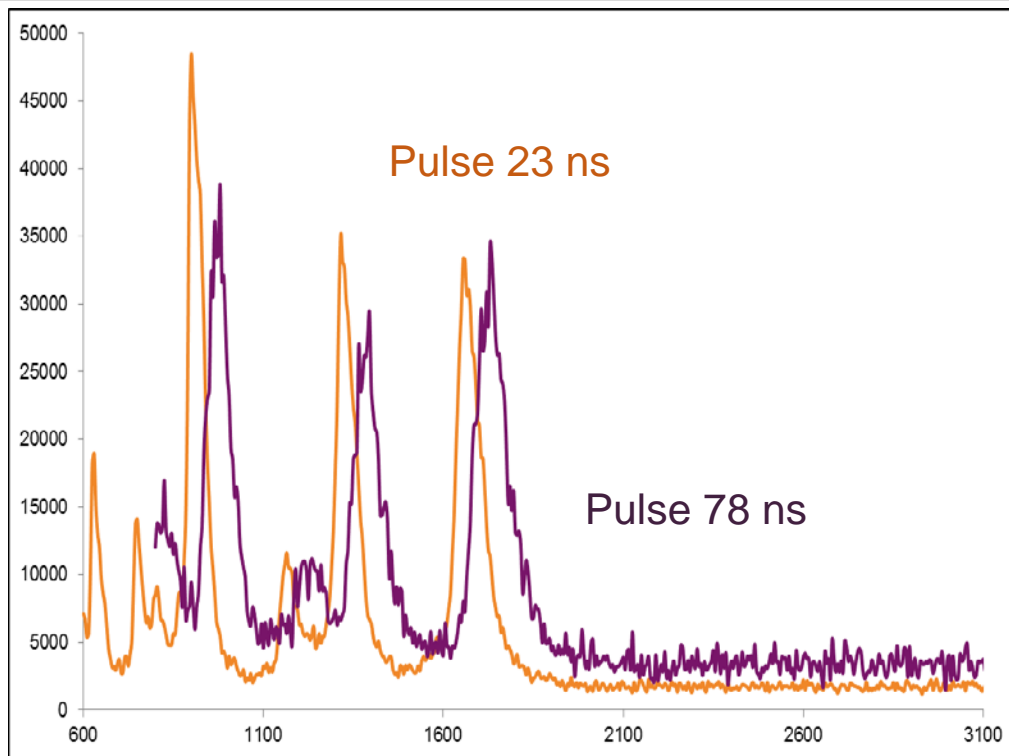
Ne, Ar, Kr, Xe 1% in helium, calibration on Xe⁺ peak, 132 uma

■ Gas identification / few air gas

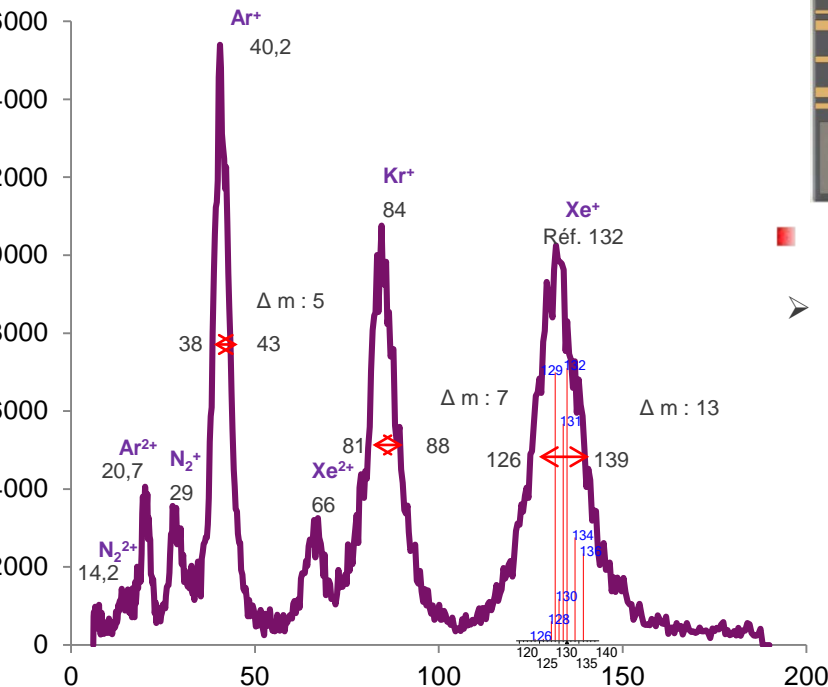
■ Broad peaks



Pulse length



- Light improvement of resolution
- Lower background (change of pulse generator)

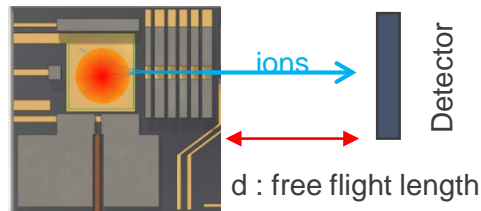


Ne, Ar, Kr, Xe 1% in helium, calibration on Xe⁺ peak, 132 uma

■ Broad peaks

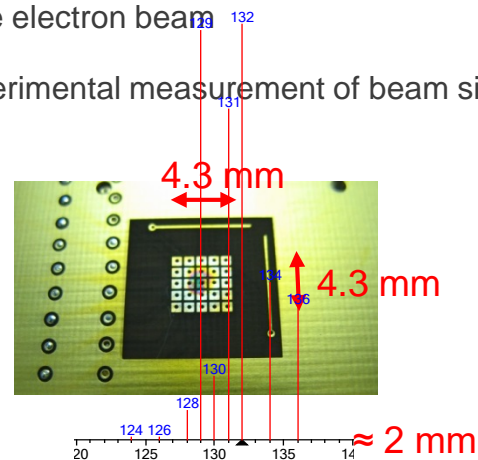
➔ Consistent with geometrical broadening / ionisation area

➔ Underlying mass isotopic group



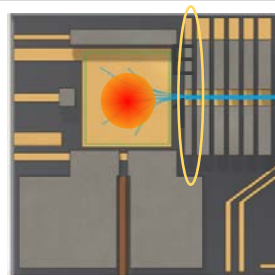
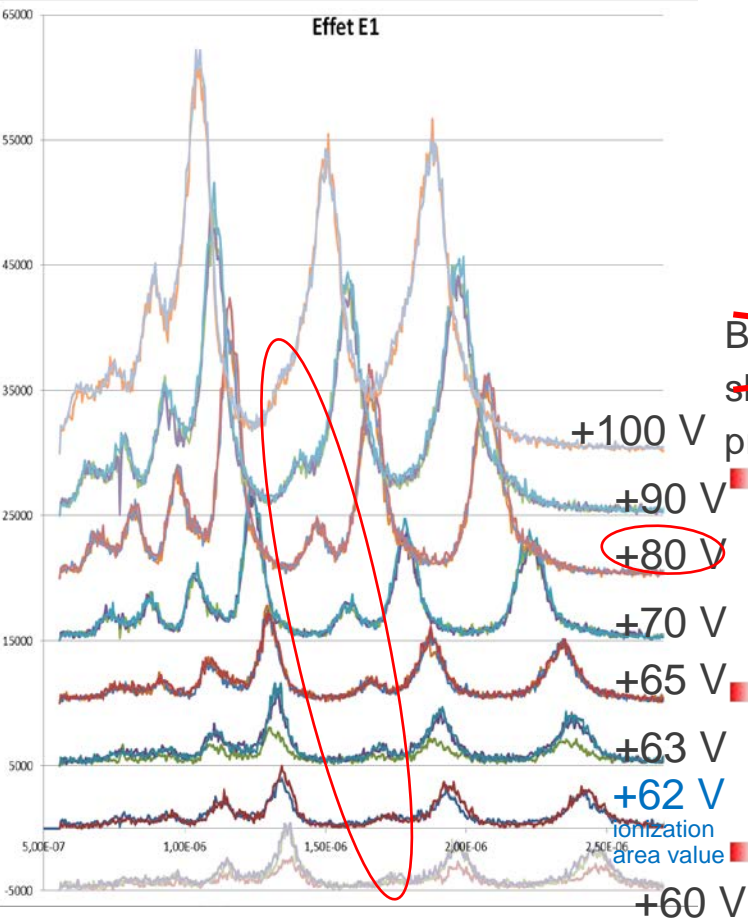
■ Pulse electron beam

➤ Experimental measurement of beam size



Theoretical mass spectrum of Xe, between 124 et 136 u, by E.I., NIST

➤ Geometrical dispersion obtained by peak elongation 1,8 mm



E1: extracting
(& focusing)

~~By simulation, a E1 voltage similar or slightly higher than ionization area is promising~~

■ Ion acceleration

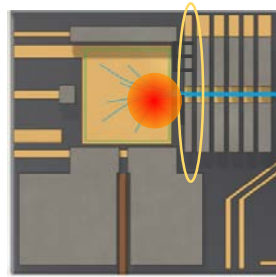
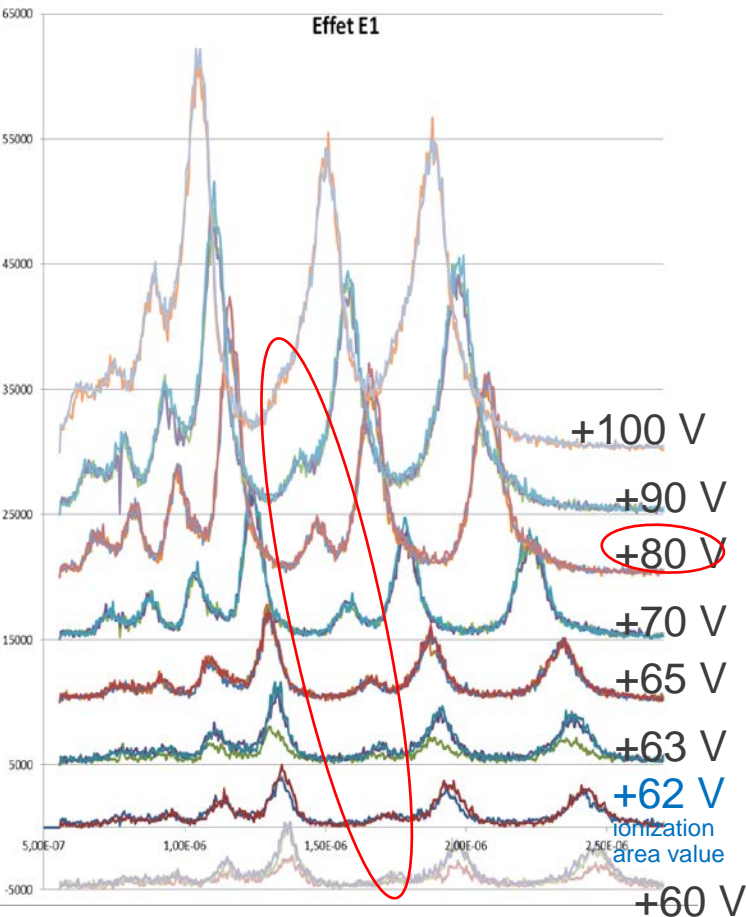
- Higher acceleration gradient, dramatical modification of accelerate voltage

■ Increasing intensities

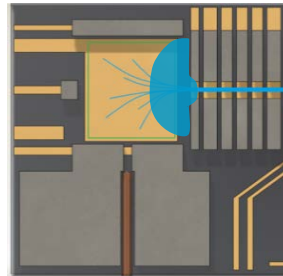
- Displacement of e beam and ionization area?

■ Enhancement of peak separation

- Better focusing, or...

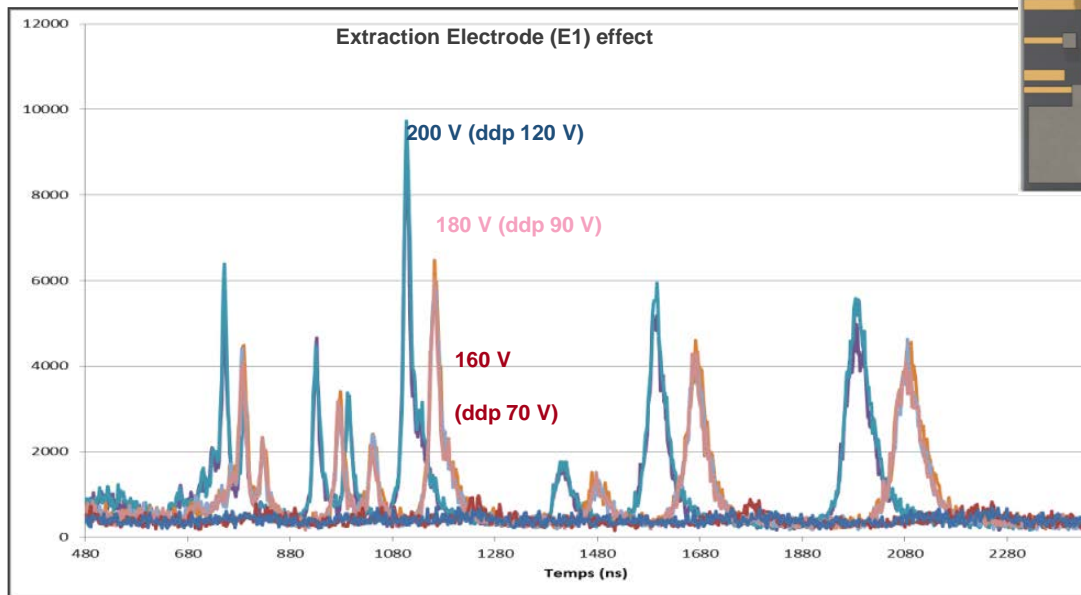


E1: extracting
(& focusing)



- Reduced ionization area
- ➡ Reduced geometric band broadening

Effect on intensity?

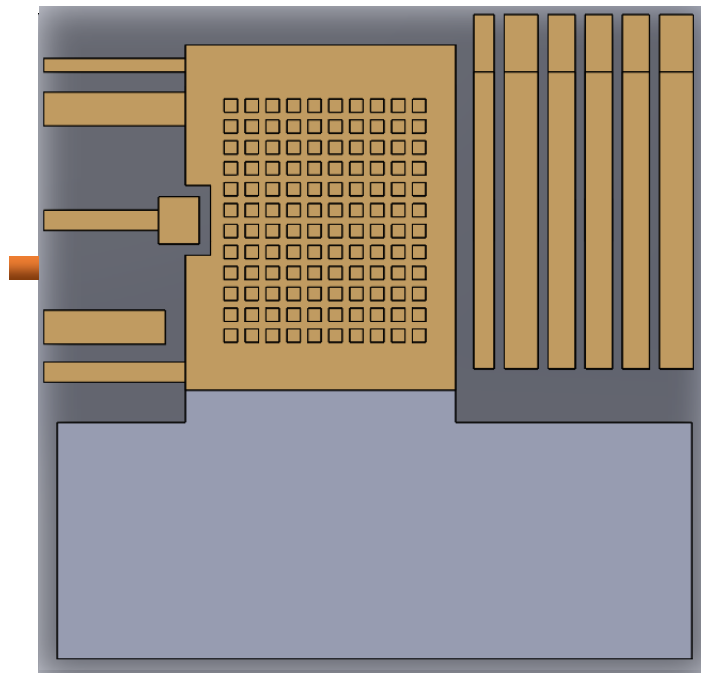


Improvement of signal intensity

Gas inlet ?

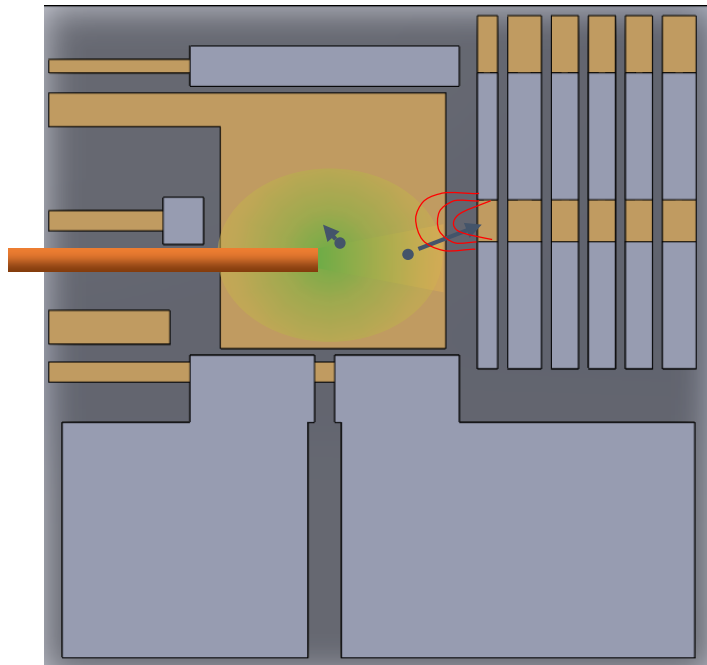
Flow Type?

- Micro-system
- 10^{-5} / 10^{-6} mbar
(rarified gas)
 - ▶ Free molecular flow
(impacts with walls /
mean free path larger than the chamber size)
 - ▶ Supersonic flow
(preferential direction)



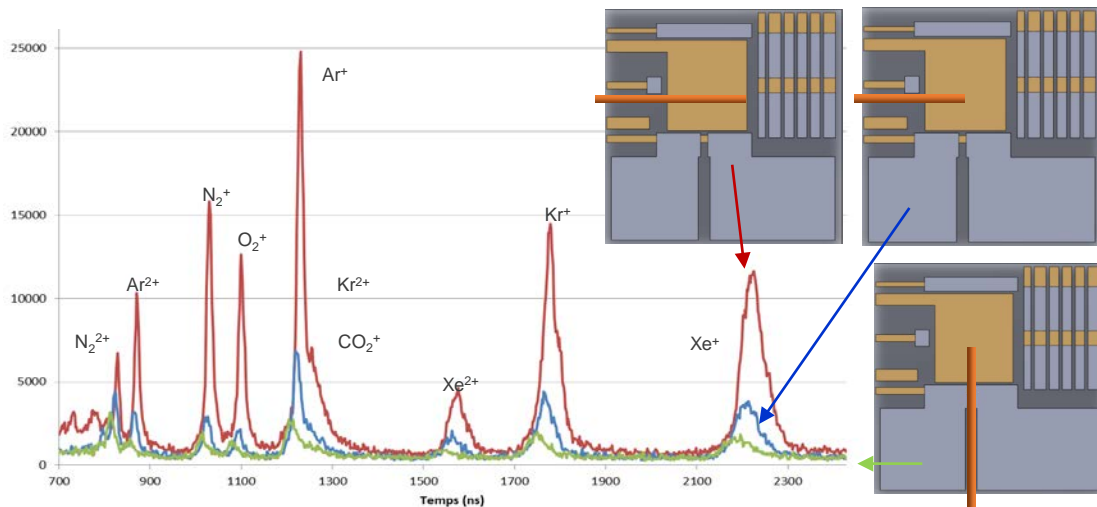
Flow Type?

- Micro-système
- 10^{-5} / 10^{-6} mbar
(rarified gas)
 - ▶ Free molecular flow
(impacts with walls /
mean free path larger
than the chamber size)
 - ▶ Supersonic flow
(preferential direction)
- Issue involves:
 - Concentration
 - Geometrical and speed band
broadening...



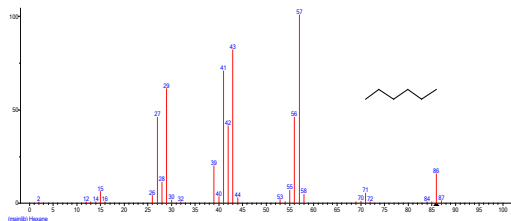
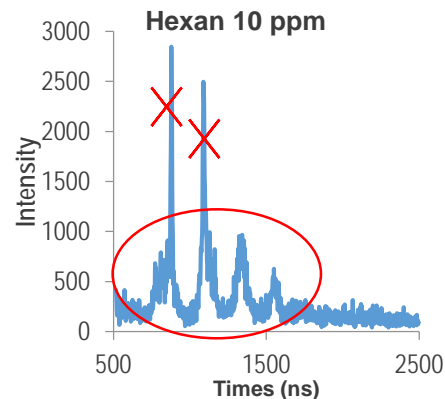
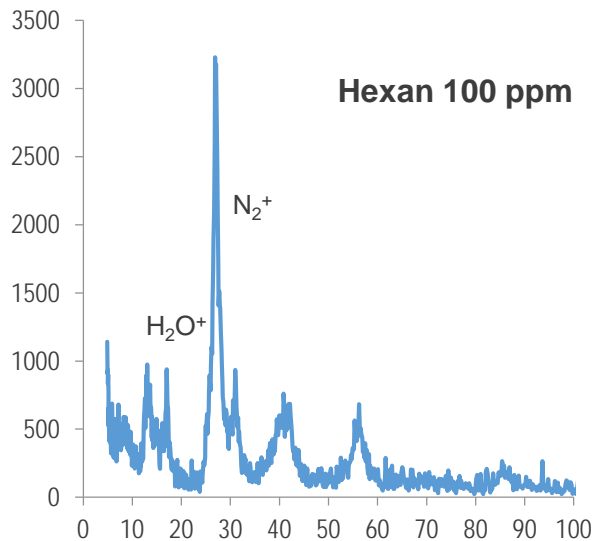
Flow Type?

- Some test on capillary position



Ar, Kr, Xe 1000ppm (v/v) dans l'hélium, $5,96 \cdot 10^{-6}$ mbar

- Support supersonic flow hypothesis



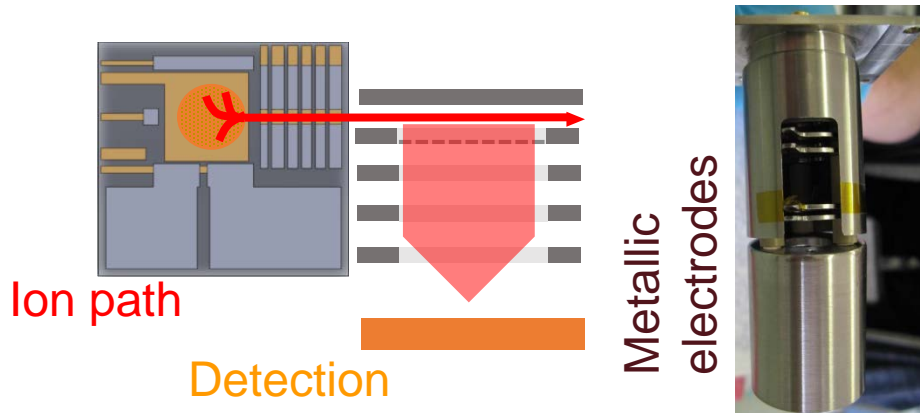
- Stabilisation of settings
- Resolution: est. 1-2 u. (masse 40)
- LD 100 ppm noble gas
- LD 10 ppm for hexane



Use as ion source

Linear μ -TOF used as ion source

- Orthogonal injection on metallic electrode assembly

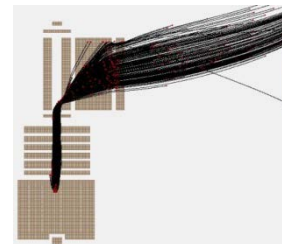


- More versatile (design, voltage...)
- Protect orthogonal Injection chip

- Orthogonal Injection on chip

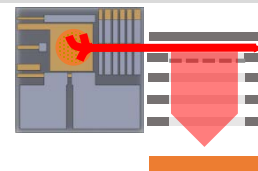


Chip assembly



Simulations

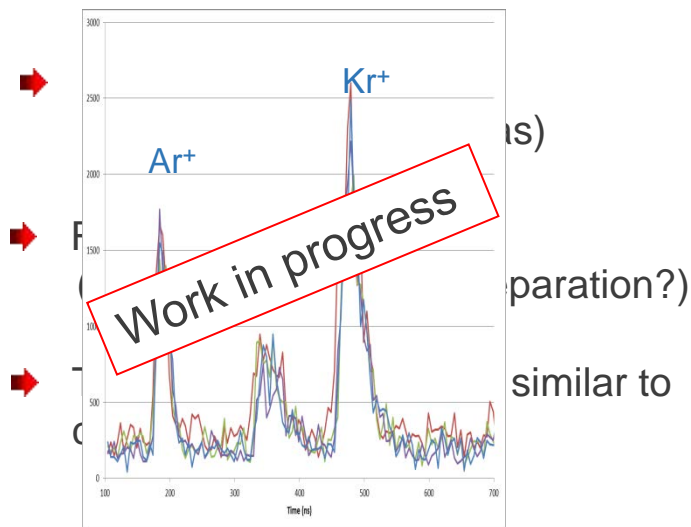
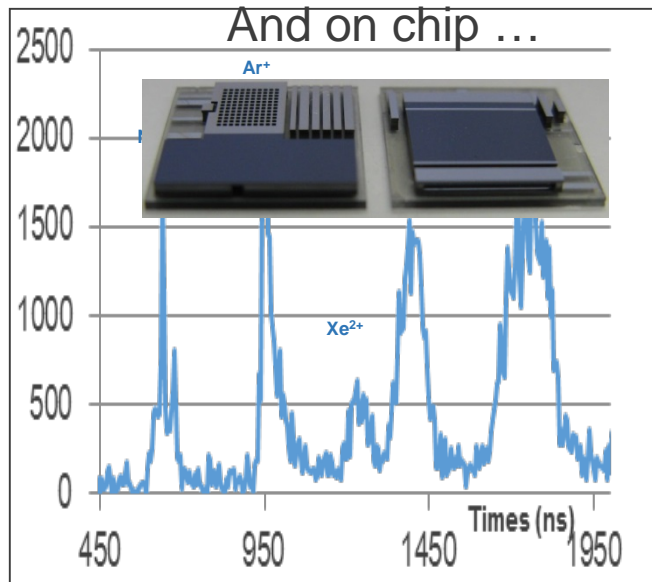
Linear μ -TOF used as ion beam source



➔ Mass Spectra



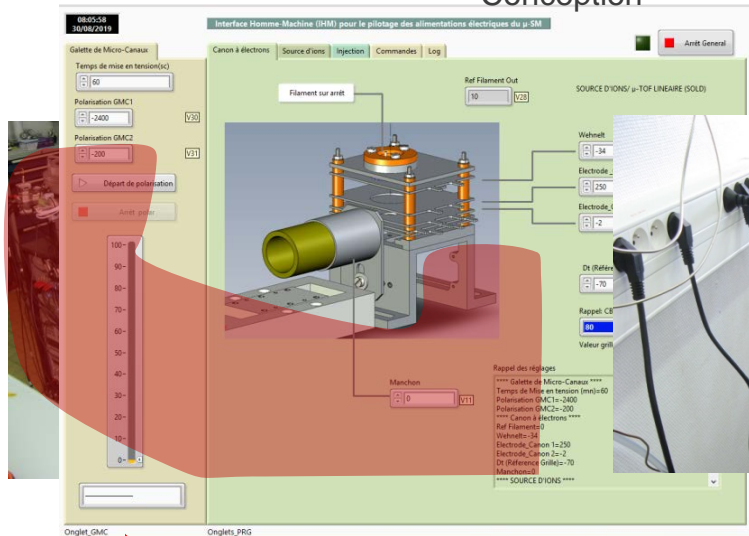
Experimental informations on the different settings



Chips Environment differentiates a source of academic curiosity and a efficient on-site device...

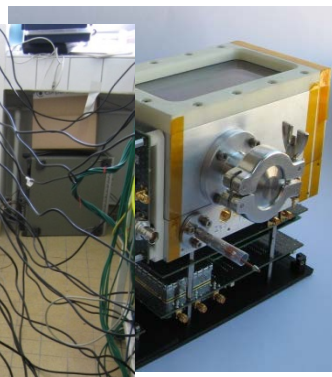
■ Power supplies / Electrostatic & Pulse control

Conception



Manufacturing & Test & burn in

18 cm



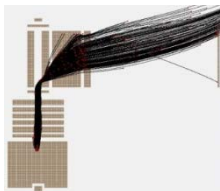
Test on linear μ -TOF



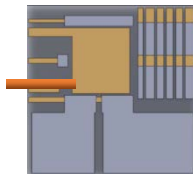
System is operational

Electrostatic & fluid Mechanics studies

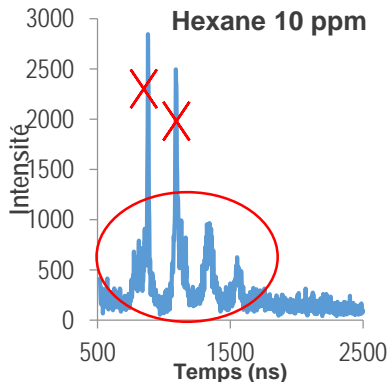
Simulations



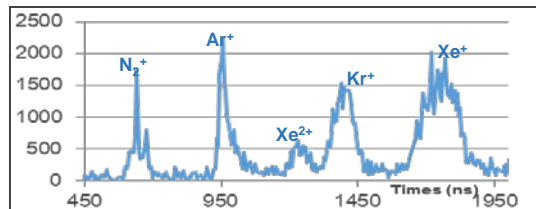
Experimental evaluation



Spectra acquisition



- More accurate set-up and adjustment, improvement of extraction and focusing performances
- Study of band broadening....



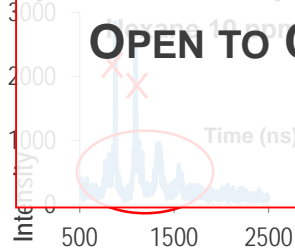
Electrostatic & fluid Mechanics studies

Simulations

Experimental evaluation

WORK IN PROGRESS...

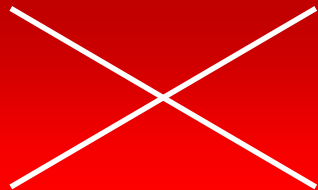
Spectra acquisition



OPEN TO COLLABORATION, EXTERNAL PARTNERSHIP...

- More accurate set-up and adjustment, focusing performances
- Study of band broadening....

2009 2010 2011 2012 2013 2014 2015 2016 2017 2018 2019



Vapor Pressure

33%

10%

1%

1%

1000 ppm

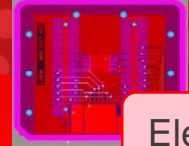
LD 100 ppm

100 ppm

LD 10 ppm

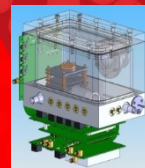


MEMS

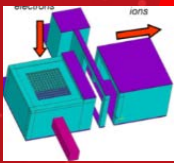


Electronic

Design & Simulations



Vacuum & fluid's mechanical

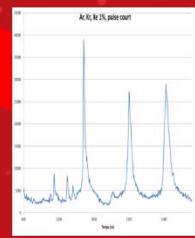


M-TOF
IN SITU
DETECTION



DE LA RECHERCHE À L'INDUSTRIE

Signal
acquisition &
processing



Electrostatic

Thank you for your attention

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